

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 61-265820
 (43)Date of publication of application : 25.11.1986

(51)Int.CI.

H01L 21/302

(21)Application number : 60-107037

(71)Applicant : ANELVA CORP

(22)Date of filing : 21.05.1985

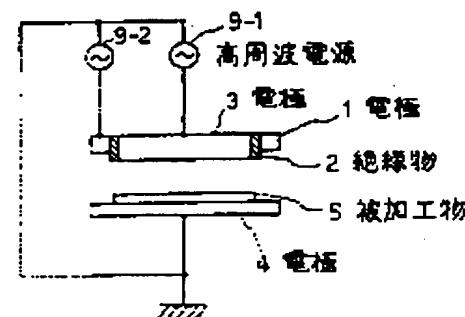
(72)Inventor : FUJIMOTO HIDEKI

(54) PLASMA TREATMENT APPARATUS

(57)Abstract:

PURPOSE: To start discharge readily at a low voltage and to prevent damages on a material to be machined, by providing a part, by which an interval between electrodes is made different, at a part of a facing electrode.

CONSTITUTION: With respect to an electrode 4, on which a material to be machined 5 is mounted, a facing electrode is divided into an electrode 1 and an electrode 3. The interval between the electrode 1 and the electrode 4 is set to be larger than the interval between the electrode 3 and the electrode 4. A specified gas is introduced in a treating tank 6. Then high frequency powers are applied to the electrodes 1 and 3 from high frequency power sources 9-1 and 9-2. When the electrode interval of 1cm or more is kept, the discharge is started readily. Therefore, the interval between the electrode 1 for starting the discharge and the electrode 4 is kept at 1cm or more. In this constitution, at first, the discharge is generated between the discharge starting electrode 1 and the electrode 4. Then, the discharge is induced and generated between the electrodes 3 and 4. Then, the high frequency power, which is supplied between the electrodes 1 and 4, is quickly turned OFF. Thus, the stable discharge is kept between the electrodes 3 and 4, and the material to be machined 5 can undergo, e.g., etching treatment.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's

decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office